

ANNOUNCEMENT | JULY 19 2017

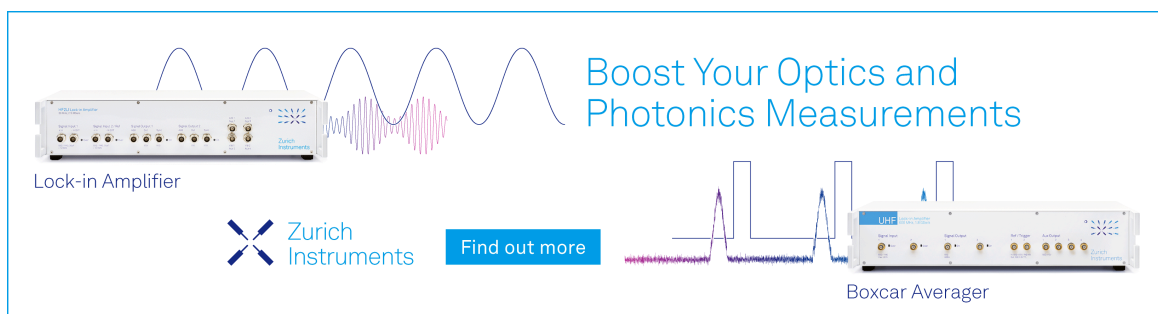
Applied Physics Letters thanks its reviewers **FREE**

Reuben T. Collins ; Eric Mills; Marie-Louise Saboungi



Appl. Phys. Lett. 111, 039801 (2017)

<https://doi.org/10.1063/1.4991645>



Boost Your Optics and Photonics Measurements

Lock-in Amplifier

Zurich Instruments

Find out more

Boxcar Averager

Applied Physics Letters thanks its reviewers

Reuben T. Collins,¹ Eric Mills,² and Marie-Louise Saboungi³

¹*Department of Physics, Colorado School of Mines, 1500 Illinois St., Golden, Colorado 80401-1887, USA*

²*AIP Publishing, 1305 Walt Whitman Road, Melville, New York 11747, USA*

³*IMPMC, Institut de Minéralogie, de Physique des Matériaux et de Cosmochimie UMR 7590 CNRS - UPMC - MNHN - IRD - Sorbonne Université, 4 place Jussieu, 75252 Paris Cedex 05, France*

(Received 22 June 2017; published online 19 July 2017)

[<http://dx.doi.org/10.1063/1.4991645>]

At the heart of the peer review process are reviewers. These researchers unselfishly donate their time and attention to review manuscripts. Their work is what makes the peer review system succeed and scholarly journals possible. The editors and publisher of *Applied Physics Letters* thank all of our reviewers for their conscientious work on behalf of the journal.

We further offer special thanks to the following researchers who have been identified as *Applied Physics Letters*' top reviewers for 2017. These individuals each reviewed multiple papers for APL, and our editors found their reviews to be consistently thorough and discerning.

M H Ansari, University at Buffalo, USA
 Seth Bank, University of Texas at Austin, USA
 Renato Buzio, National Research Council (CNR), Italy
 Bing-Yang Cao, Tsinghua University, China
 Sonal Dey, SUNY Polytechnic Institute, USA
 Zhenxing Feng, Oregon State University, USA

Xiaojun Hu, Zhejiang University of Technology, China
 Yuan Huang, Brookhaven National Laboratory, USA
 Wanjun Jiang, Tsinghua University, China
 Janesh Kaushik, Solid State Physics Laboratory, India
 Yong-Chang Lau, National Institute for Materials Science, Japan
 Emil List-Kratochvil, Humboldt-Universität zu Berlin, Germany
 Guanxiong Liu, University of California, Riverside, USA
 Eric Yue Ma, Stanford University, USA
 Takahiro Mise, Toyota Central R&D Labs., Inc., Japan
 John Robertson, University of Cambridge, UK
 Kechao Tang, Stanford University, USA
 Zhiyong Wang, University of California, Riverside, USA
 You Zhou, Harvard University, USA
 Taishan Zhu, University of Illinois at Urbana Champaign, USA